



MNT Roadmaps

4M2C PATRIC SALOMON GmbH, Berlin, Germany
-- enablingMNT Group --

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www.enablingMNT.com



NEXUS

International Technology Roadmap for Semiconductors (ITRS), updated annually



Table 4: Packaging Challenges through 2007

Difficult Challenges (Through 2007)	Summary of Issues
Improved organic substrates	T _g (Glass Transition Temp.) compatible with lead-free solder processing
	Increased wireability at low cost, substrates are a barrier to flip chip adoption
	Improved impedance control and lower dielectric loss for high-frequency applications
	Improved planarity and low warpage at higher process temperatures
	Low moisture absorption
Improved underfills for flip chip on organic substrates	Low-cost embedded passives
	Improve flow, fast dispense/cure, better interface adhesion, and low absorption
	Higher operating range for automotive and Pb free solder dispense underfills
Coordinated design tools & simulators to address chip, package, and substrate co-design	Improved adhesion, small filler size, and improved flow characteristics of underfills
	Chip, package, and system level co-design tools
	Educational programs required to train engineers in chip, package, and substrate co-design
	Faster analysis tools for integrated thermal/mechanical design
Impact of Cu/low κ (dielectric constant) on packaging	Higher accuracy, faster electrical simulation capabilities
	Direct wirebond and bump to Cu (Copper)
	Bump & underfill technology to assure low κ dielectrics
Pb (lead), Sb (antimony), and Halogen free packaging material	Improved Mechanical strength of dielectrics
	Interfacial adhesion
Difficult Challenges (Beyond 2007)	
	Package cost which may greatly exceed die cost
	Reliability under thermal cycling (stress and moisture)
	Research investments required for packaging cost reduction are decreasing

Table 93a Single-chip Packaging Technology Requirements—Near-term

Chip Size (mm ²) [3]	100	100	100	100	100	100	100
Low-cost	100	100	100	100	100	100	100
Cost-performance	140	140	140	140	140	140	140
High-performance	310	310	310	310	310	310	310
Harsh	100	100	100	100	100	100	100
Maximum Power (Watts/mm ²) [4]							
Low-cost (Watts) [1]	2.5	2.7	2.8	3	3	3	3
Cost-performance	0.57	0.6	0.65	0.7	0.74	0.78	0.83
High-performance	0.48	0.61	0.64	0.68	0.81	0.84	0.84
Harsh	0.14	0.18	0.18	0.18	0.18	0.2	0.2
Core Voltage (Volts)							
Low-cost	1.2	1.2	1	0.9	0.9	0.8	0.8
Cost-performance	1.2	1.2	1	0.9	0.9	0.8	0.8
High-performance	1.2	1.2	1	0.9	0.9	0.8	0.8
Harsh	2.5	2.5	1.2	1.2	1.2	1.2	1.2
Package Pincount Maximum [5][6]							
Low-cost	112-408	122-500	134-550	144-800	160-860	180-720	180-800
Cost-performance	600-1462	600-1600	560-1760	550-1936	800-2140	800-2400	880-2800
High-performance							
Harsh							

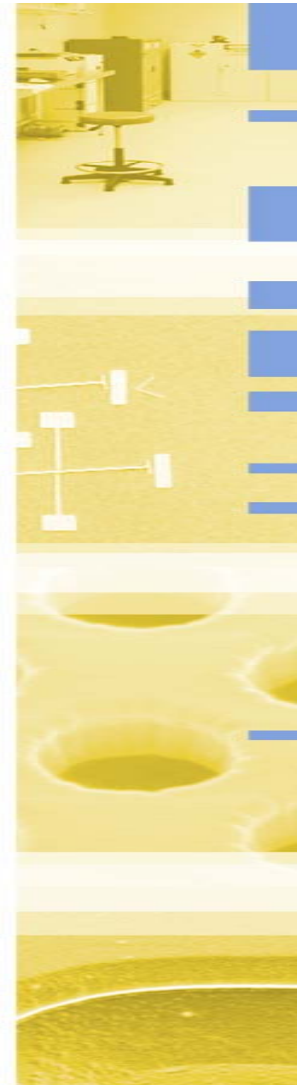
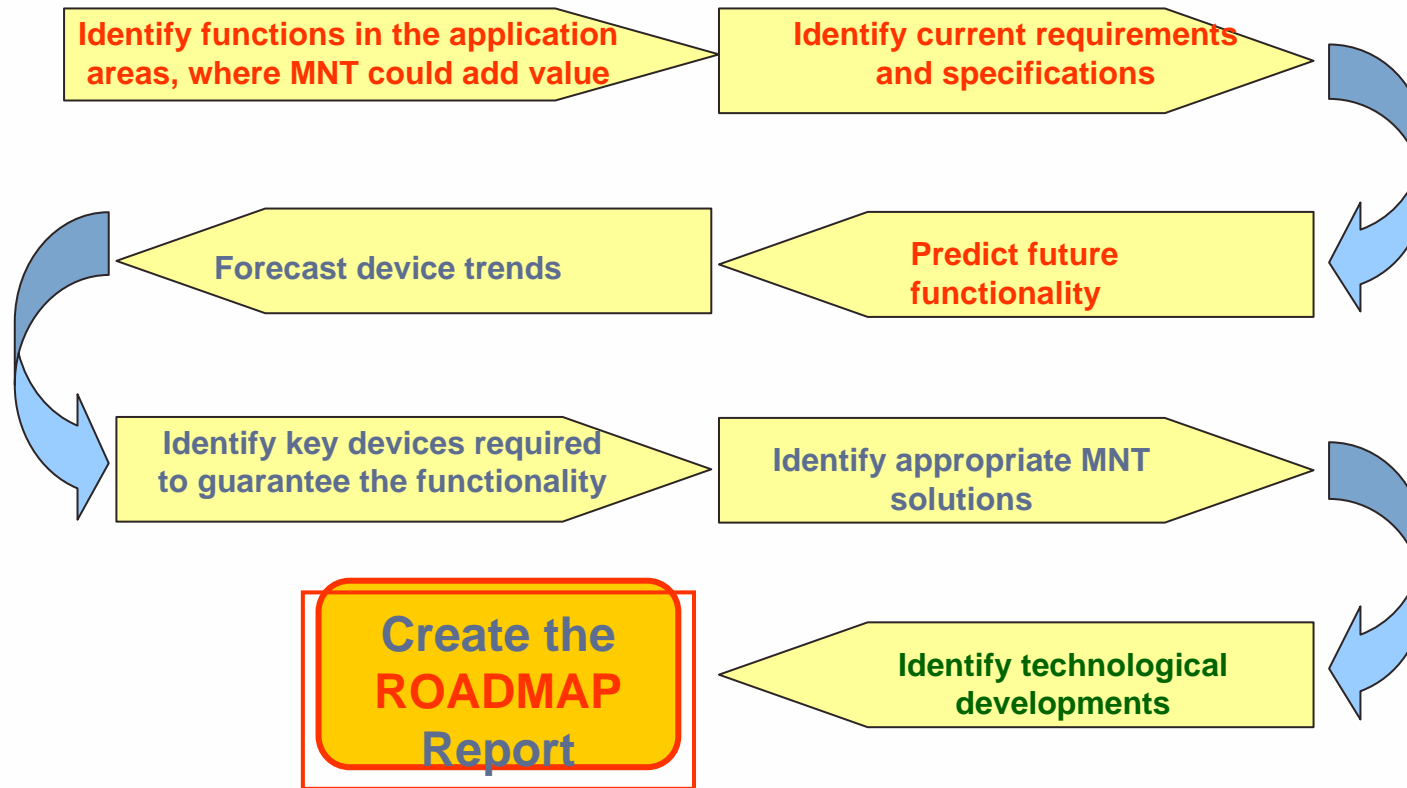
TECHNOLOGY DEVELOPMENTS NEEDED TO ADDRESS THESE CHALLENGES

HIGH-LEVEL CHALLENGES AND RELATED ISSUES

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Methodology of the NEXUS Roadmap

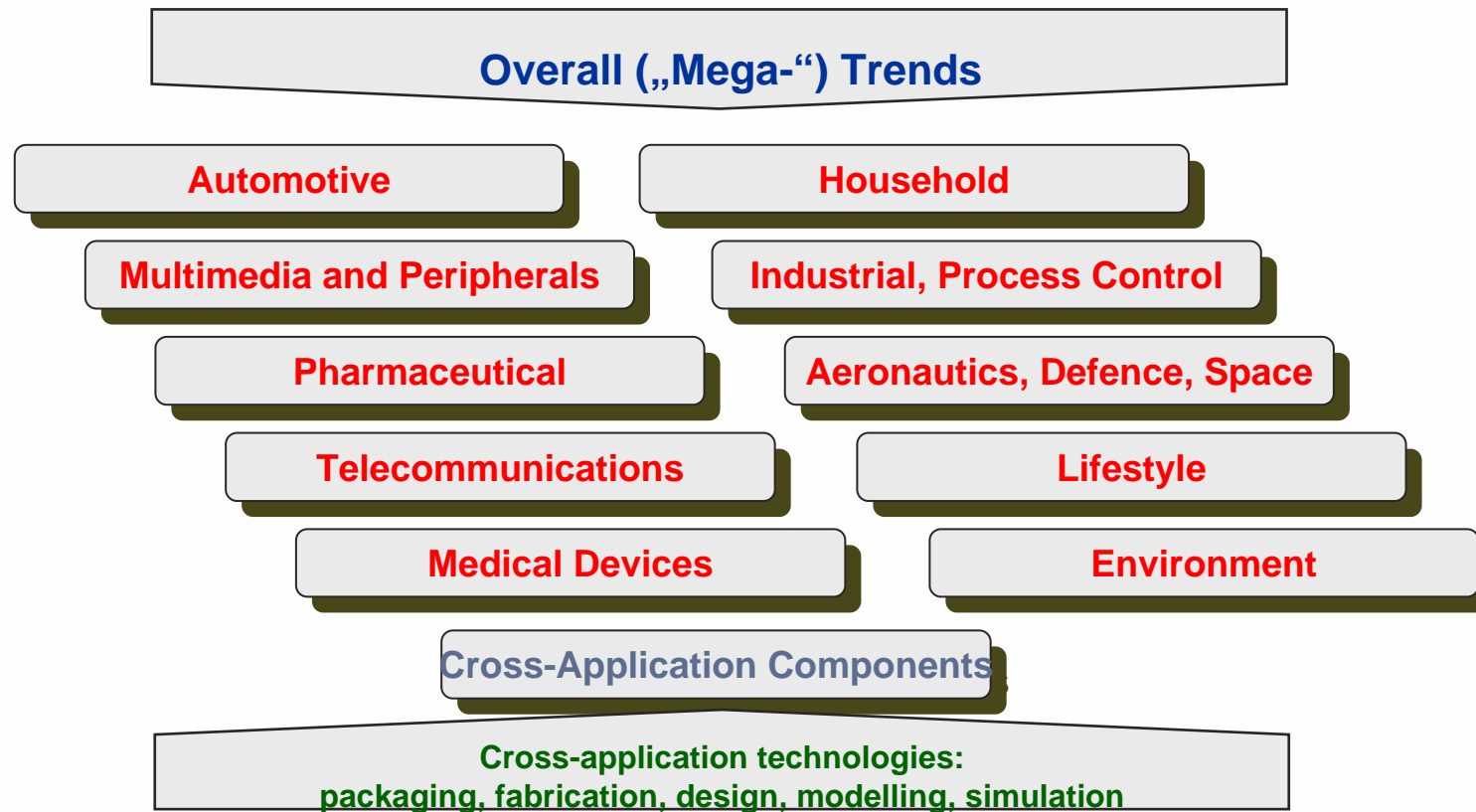


Source: NEXUS Association, 2000, 2003

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NEXUS Roadmap: Application Domains

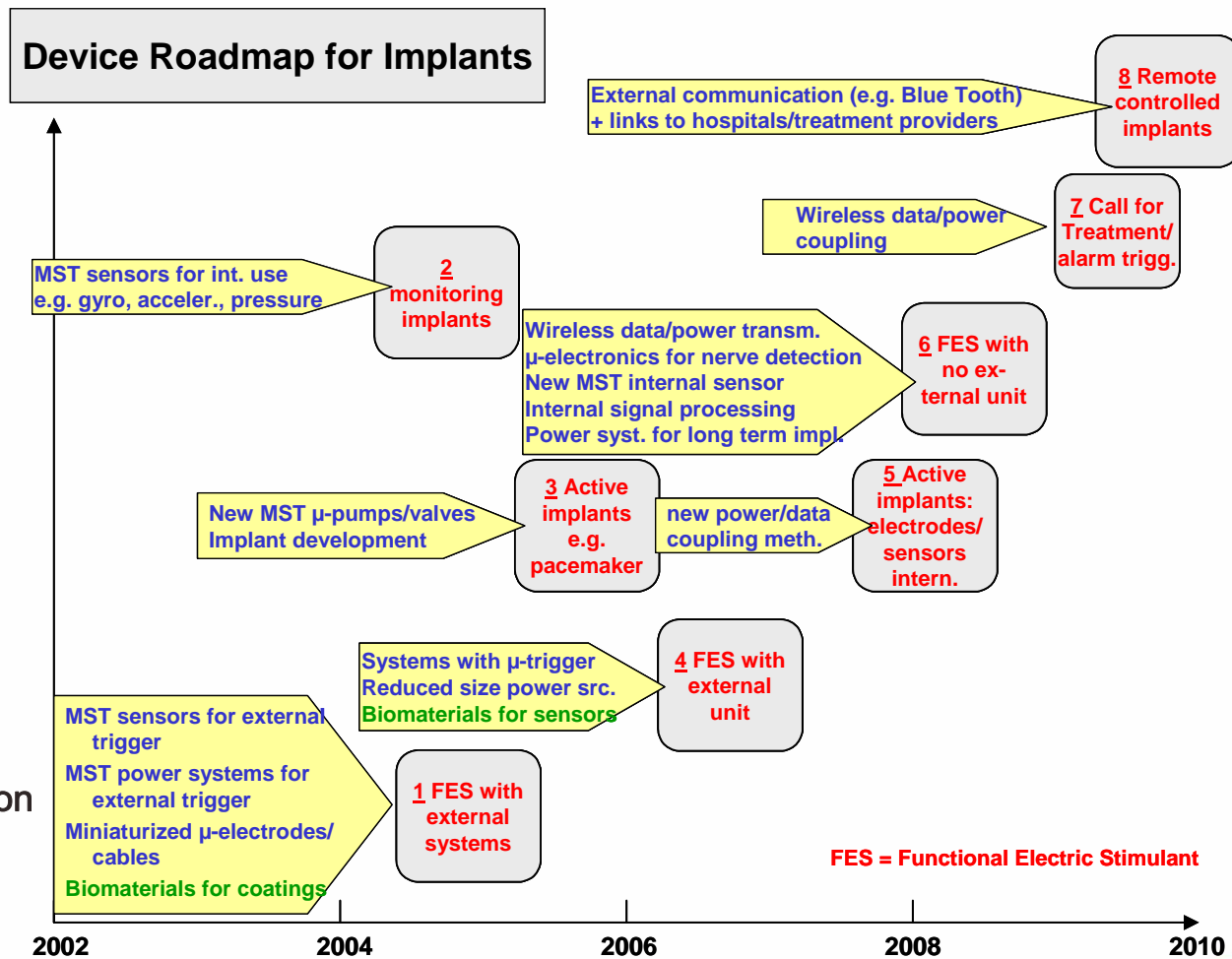


Source: NEXUS Association, 2003

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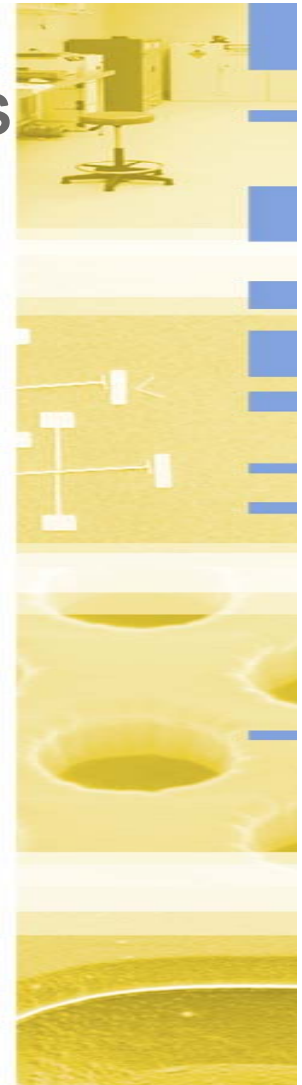


NEXUS Roadmap: Medical Applications



Source:
NEXUS Association
2003

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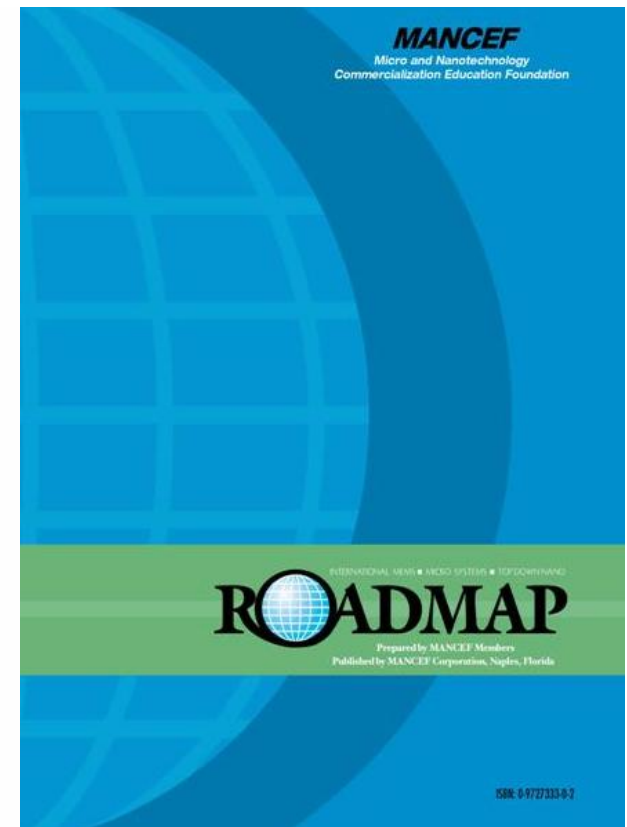


MANCEF International Micro-Nano Roadmap 2nd Edition, 2004

MANCEF
www.mancef.org

Contents

1. Executive Summary
2. Introduction
3. RF MEMS
4. Nanotechnology
5. MEMS Patent Review
6. Microtechnology Process Flows and Equipment Infrastructure Equipment And Tooling For MNT
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8. MEMS Packaging and Assembly

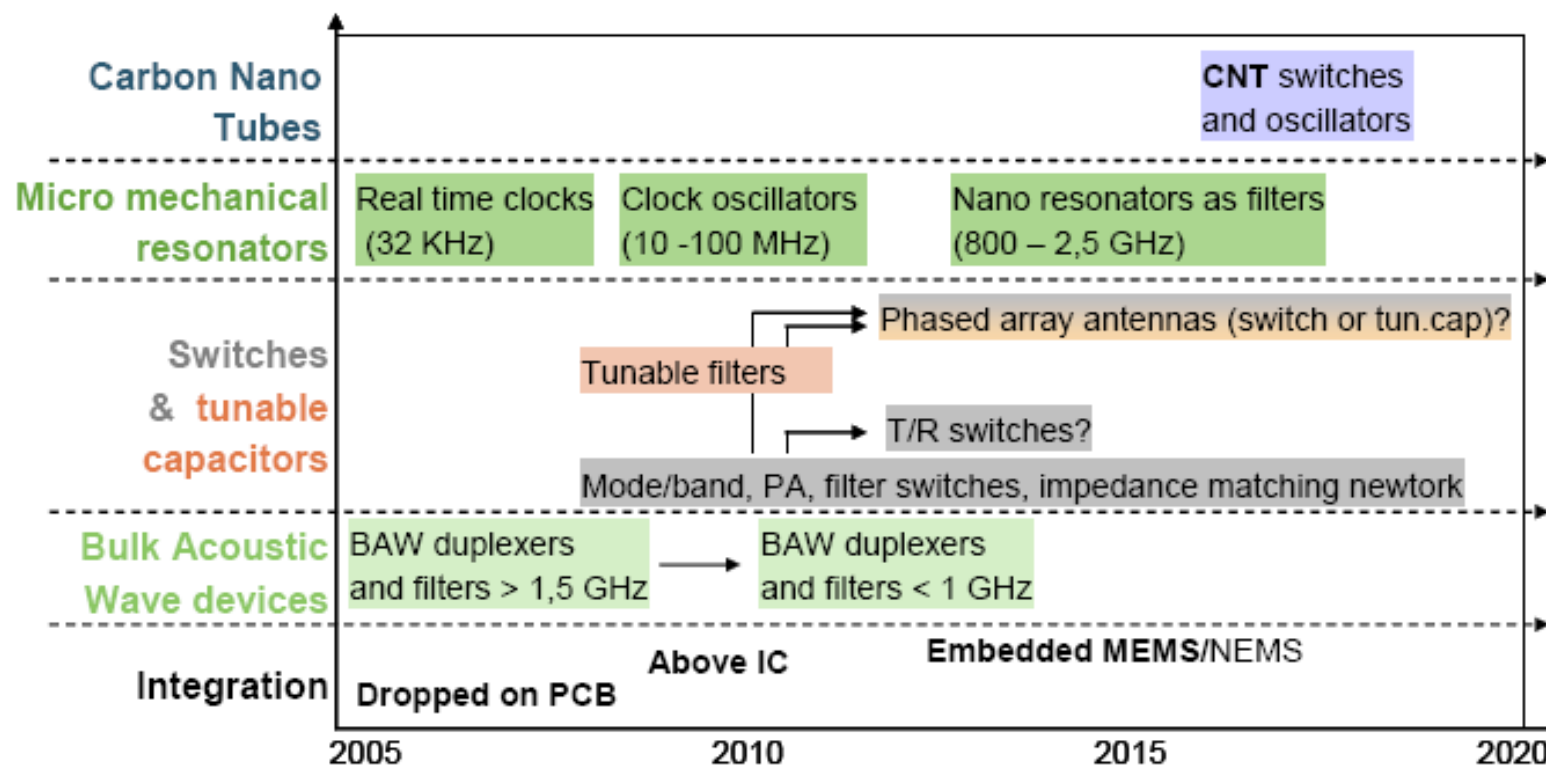


Source: Mancef, 2002, 2004

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MIMOSA Integrated Project: Ambient Intelligence Roadmap



Roadmap of micro-nano HW technology for communication in Ambient Intelligence

www.mimosa-fp6.com

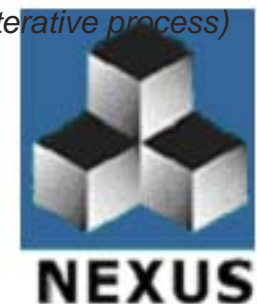
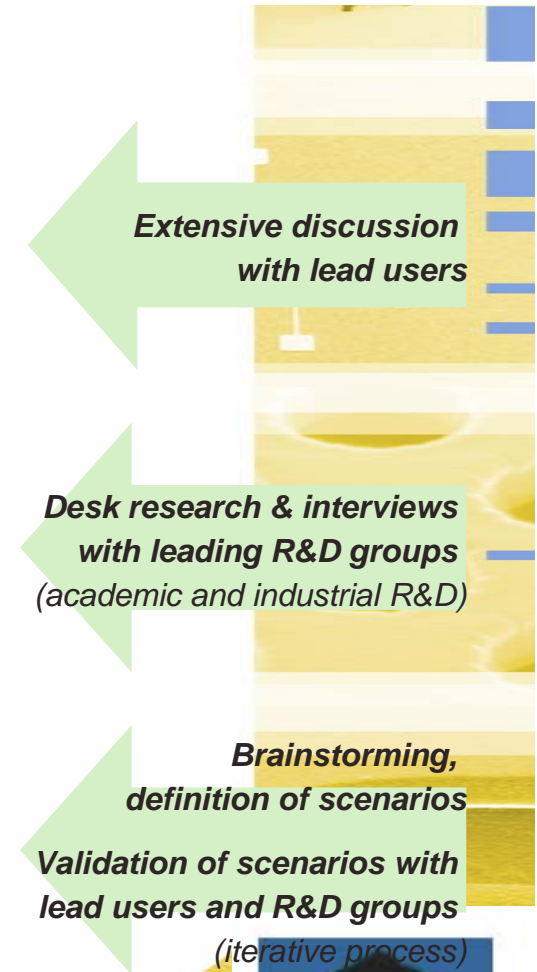
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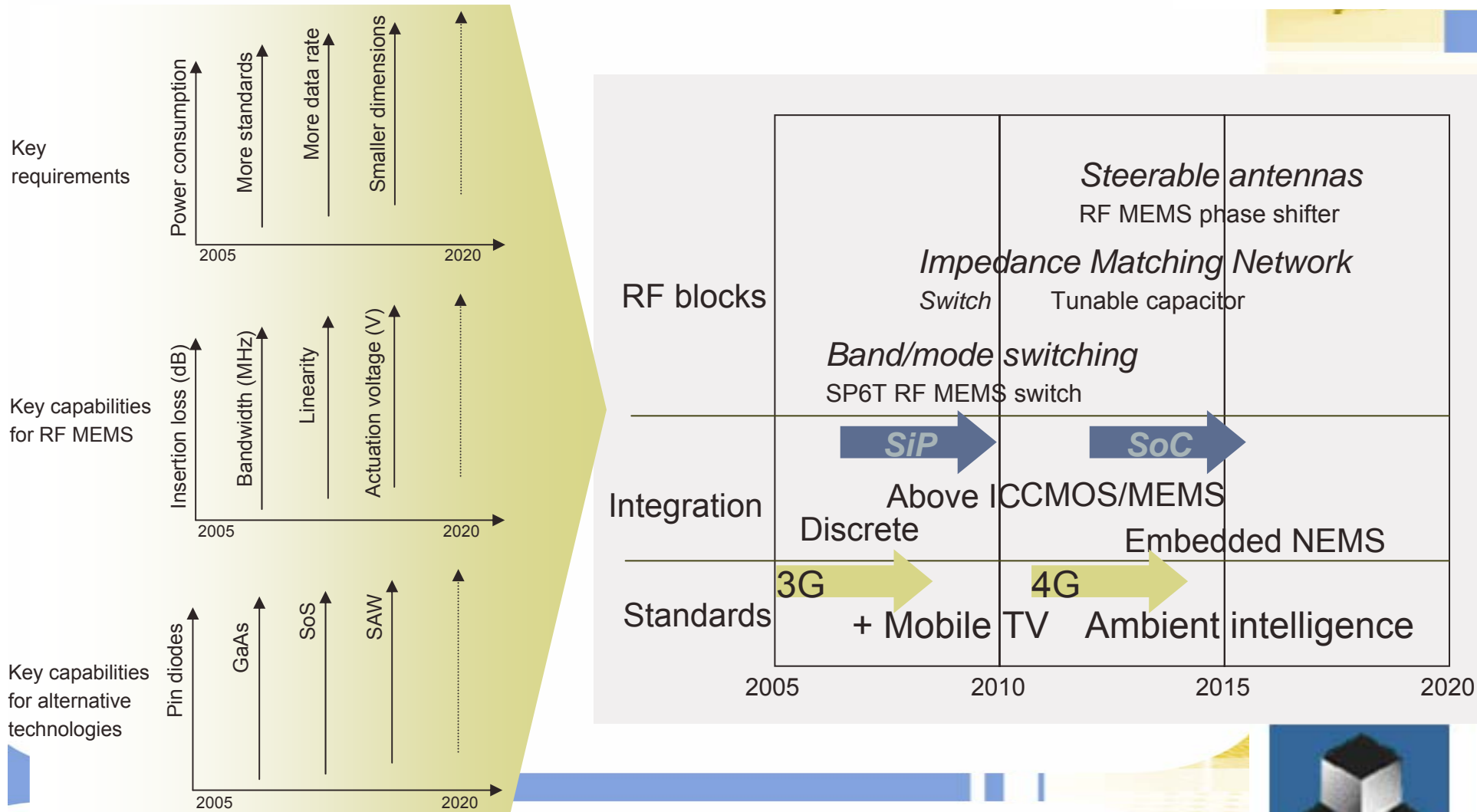
ARRRO - Applied Research Roadmaps for RF MEMS Opportunities: Roadmapping process



- Define where we want to go
 - Define a list of **key capabilities**: technical parameters relevant to assess the impact of the technology for each application.
 - Define objectives in 5 to 15 years with regard to key capabilities
- Define where we are today
 - Quantifying performance / key capabilities today of RF MEMS as well as competing technologies
 - Identify limits of technologies, options for improvements
- Define how to get there
 - Define scenarios for evolution of the technology
 - Create single graphs roadmappings/ key capability
 - Create scenarios for overall roadmap



ARRRO - example: mobile handsets



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EC Working Group on NanoManufacturing

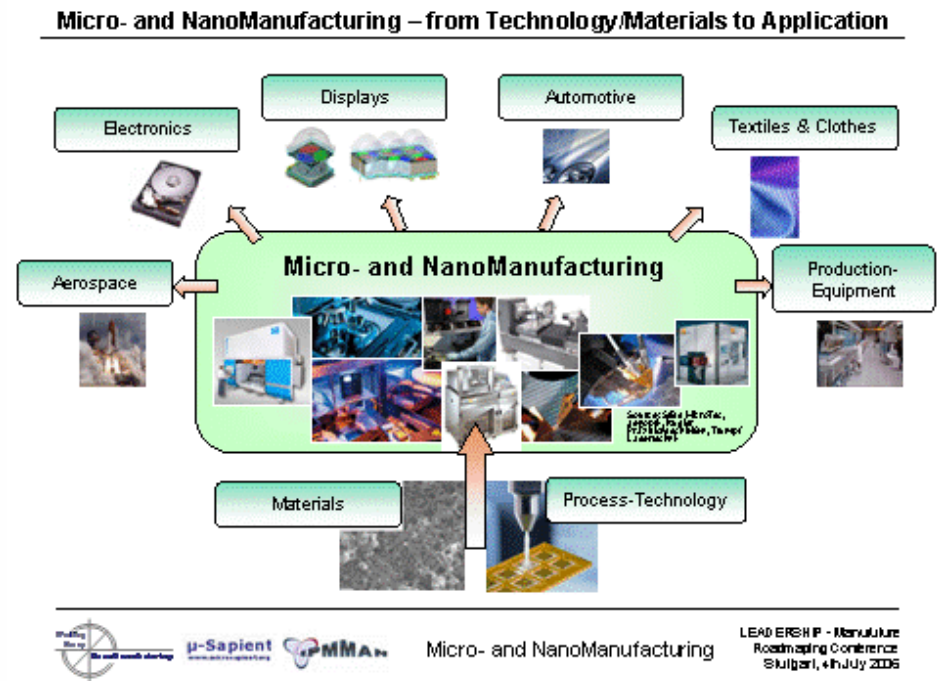


“Vision and Strategic Research Agenda” of NanoManufacturing forum

- Strategy paper January 2006
- 1st Questionnaire and first evaluation Meeting January 2006
- Expert groups: 49 experts and 6 coordinators
- Draft for 1st Input 7th framework → EC

Members of the working group

- 200 Persons (mailing list / member list)
- 80 companies and research institutes
- networks and projects are involved
- about 40 participants in each meeting



www.nanomanufacturing.eu

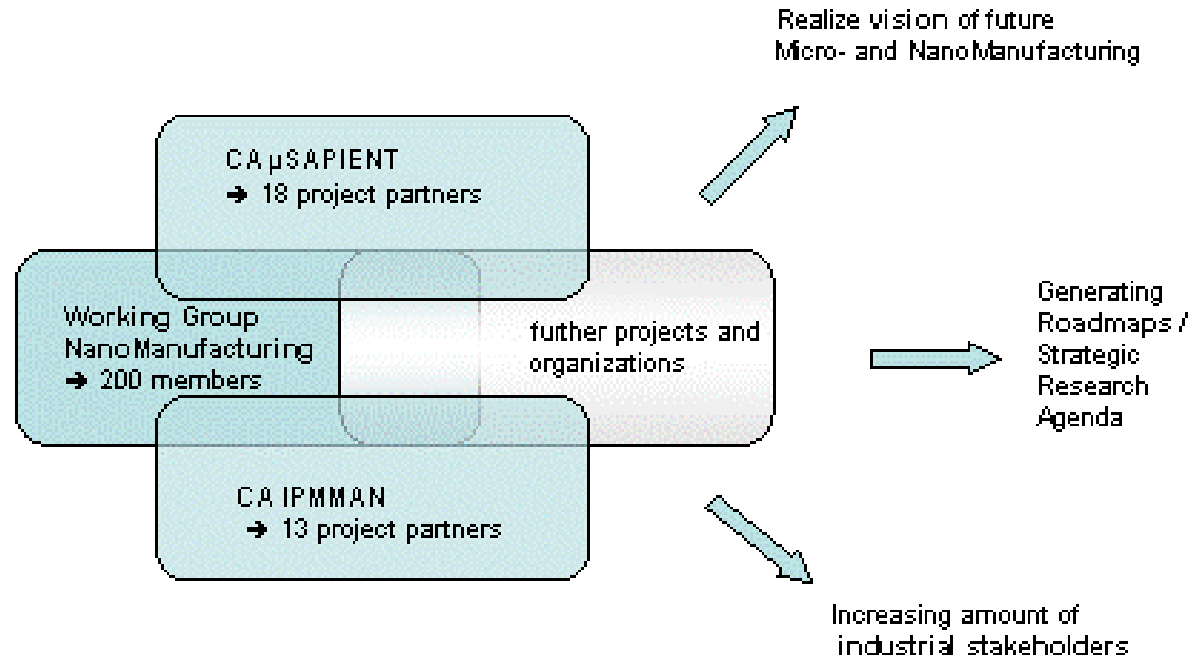
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EC Working Group on NanoManufacturing



A new Micro- and NanoManufacturing community is ready to succeed



μ-Sapient



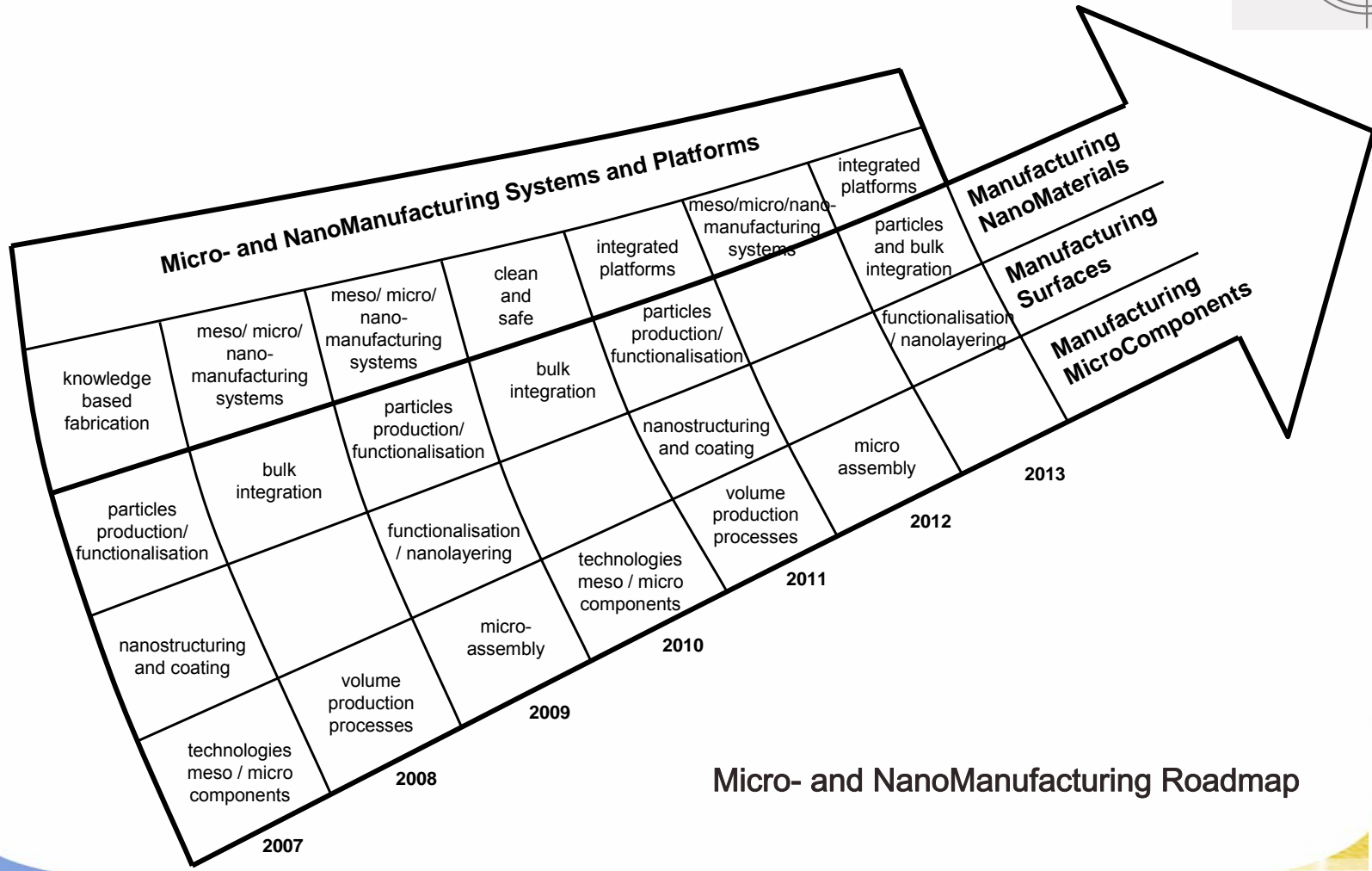
Micro- and NanoManufacturing

LEADERSHIP - Manufacture
Roadmapping Conference
Stuttgart, 4th July 2006

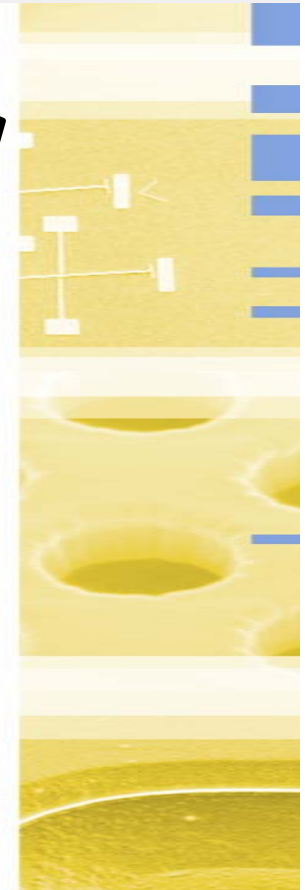
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EC Working Group on NanoManufacturing



Micro- and NanoManufacturing Roadmap



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EC 4M Project: Application Requirements for 4M Manufacturing Technologies

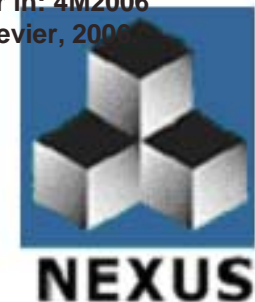


Application requirement	Perceived Importance
A Low cost / volume production	
B Interdisciplinary, design, and process/technology knowledge	
C 3D features, surface properties	
D Technology / maturity / standards	
E Function and physical integration	
F Quality/reproducibility/reliability	
G New/improved/multi materials	
H Integrated process chains	
I Process / machine technologies	
J Assembly & packaging	
K Nano-micro or micro-meso integration	

Researchers
 Industry

A roadmapping study in Multi-Material Micro Manufacture. S.S. Dimov, C.W. Matthews, A. Glanfield, P. Dorrington. To appear in: 4M2006 Second International Conference on Multi-Material Micro Manufacture Proceedings, eds. W Menz, B Fillon, and S Dimov, Elsevier, 2006

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EC 4M Project: Importance of 4M Manufacturing Technologies

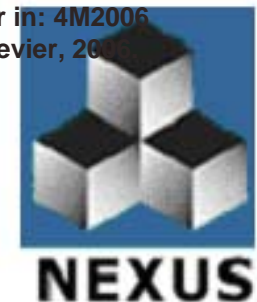


Technology	Perceived importance
3D Printing	
Milling	
Powder injection moulding	
Reel to reel embossing	
Nanoimprint lithography (NIL)	
Injection moulding	
Nanoimprinting	
Multi-component injection moulding	
Laser ablation	
Selective laser sintering	
Metal Forming	
Plasma machining	
E beam lithography	

Researchers
 Industry

A roadmapping study in Multi-Material Micro Manufacture. S.S. Dimov, C.W. Matthews, A. Glanfield, P. Dorrington. To appear in: 4M2006 Second International Conference on Multi-Material Micro Manufacture Proceedings, eds. W Menz, B Fillon, and S Dimov, Elsevier, 2006

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EPoSS - European Technology Platform on Smart Systems Integration



TOWARDS A VISION OF INNOVATIVE SMART SYSTEMS INTEGRATION



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www.smart-systems-integration.org

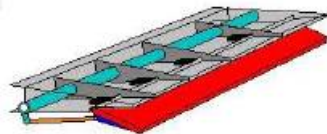
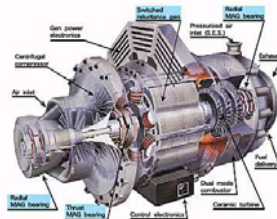
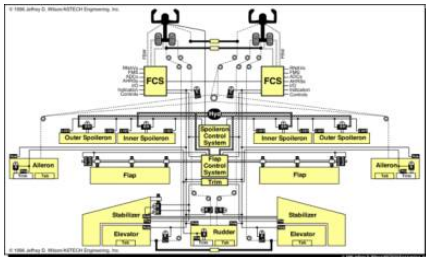
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EPoSS – from the Strategic Roadmap on Aeronautics (draft)

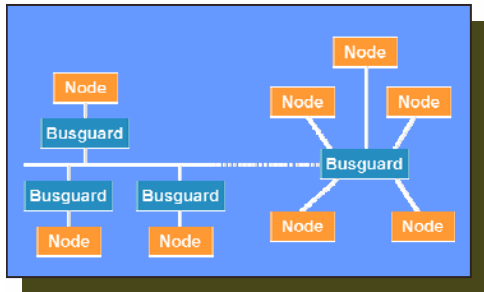


The electrical aircraft



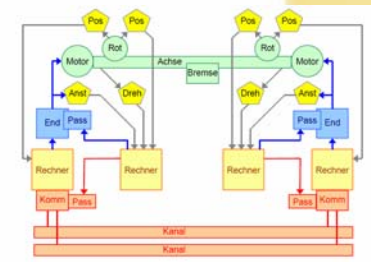
By-light functions
Next generation of optical components and optical sub-systems

Fuel cell APU
Sensors, process monitoring and control



By-wire functions
Smart sensors and actuators

Electrical power management
Detection and control devices for power network

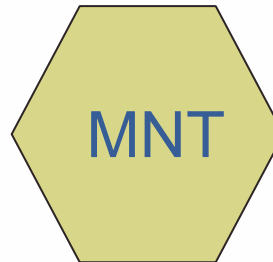


Network of Excellence: Design for Micro & Nano Manufacture (PATENT-DfMM)"



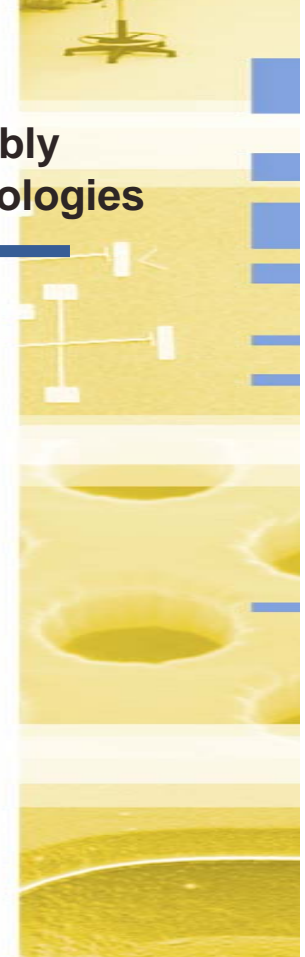
DfM – yield enhancement, robustness, testability

Microelectronics



DfM – part count, assembly process, design methodologies

Manufacturing



Objectives:

- Integrate European Research in DfMM
- Offer services to industry, especially SMEs:
 - Research type services
 - Databases: Failure modes, packaging and test solutions, etc.
 - Consulting: Improve production processes, test, yield, reliability, etc.
 - Design services
 - Subsystem development
 - Training courses, education

www.patent-dfmm.org

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1 - Constitution of High Level Challenges and Related Issues Table

- Questionnaires + browsing through existing deliverables from the project
- 1st workshop (30 experts, half industrialists) at Heriot-Watt in February 2006

Summary of issues	(S)hort/(Me)diu(m)/(L)ong term	Priority (H / M / L)	RF / MOEMS / Both
Reducing costs of packaging	M/L	H	Both
Integrating active and passive components	M	H	Both
Development/integration of new materials for higher resonant frequencies	M	H	Both
Technologies that allow in-package tuning of RF devices	M	H	RF
Development/integration of new materials for higher resonant frequencies	S/M	H	RF
Development/integration of new materials for higher resonant frequencies	M	H	Both
Technologies that allow in-package tuning of RF devices	M	H	RF
Surface treatment of structures to prevent molecular absorption	S/M	H	RF

2 – Constitution of Technology Requirements for selected Challenges

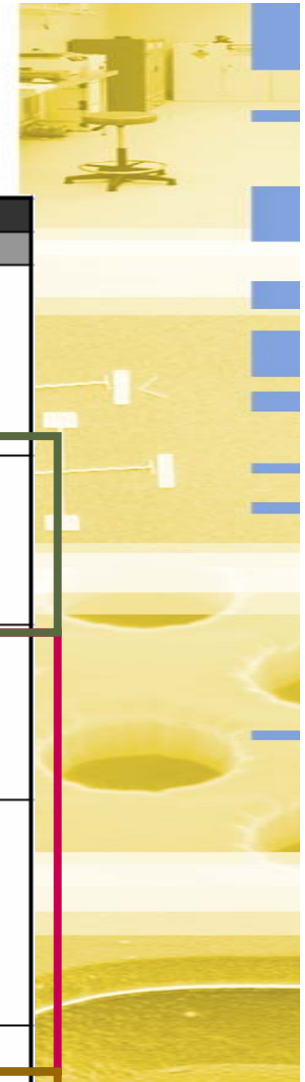
- Choice of a High-Level Challenges by experts
- 2nd workshop at Fraunhofer IZM in June 2006

3 – Write - up Roadmap

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PATENT-DfMM Project: Packaging Roadmap



	Short term			Middle term				Long term		
	2006	2007	2008	2009	2010	2011	2012	2013	2014	2015
Market drivers										
Challenges metrics	PATENT-DfMM paper studies / Roadmapping sessions									
Package challenges		Low cost WLP		Improvements in CAD/Modelling		Improved reliability		Future packages		
R&D projects to tackle issues	Patterning capabilities for getters				Definitions of safety margins					
		standard for hermetic packaging for micro-cavities								
Enablers	Access to toe-dipping finance		Interviews IAB members					Access to commercial WLP service		

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PATENT-DfMM Project:

Next Roadmapping Activity (Sept 2006 – March 2007):

Design, Modeling, Simulation Tools

Workshop: 25-26 Jan 2007, Berlin

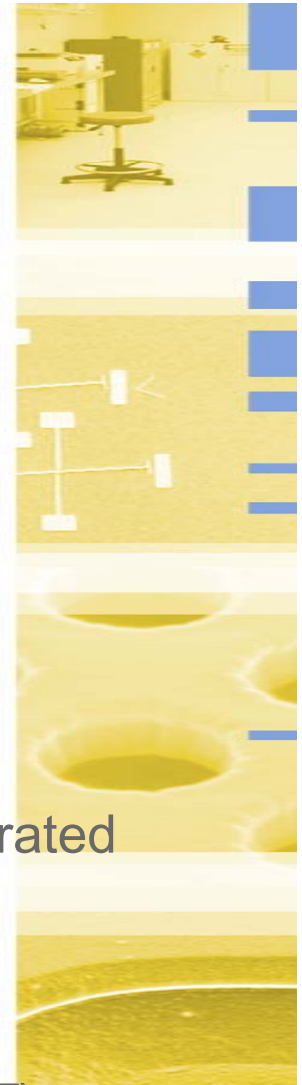
- User needs
- Tool company plans / roadmaps
- Research/development needed to improve software
- New projects / Funding needs

Contributions/collaboration needed for Roadmap:

- (Industrial) users of software tools (fabless designers, integrated manufacturers, etc)
- Suppliers/vendors of software tools
- Existing roadmaps/reports: Mancef, MIG, NEXUS

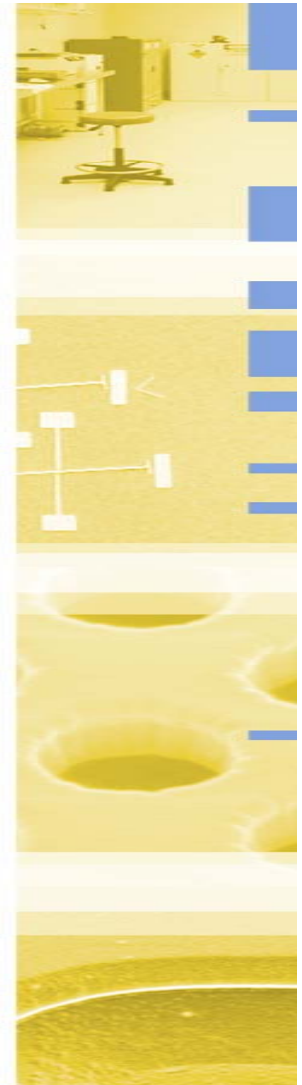
Contact: Dagmar Peters (Univ. Bremen), Patric Salomon (4M2C / enablingMNT)

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Other Roadmapping Activities

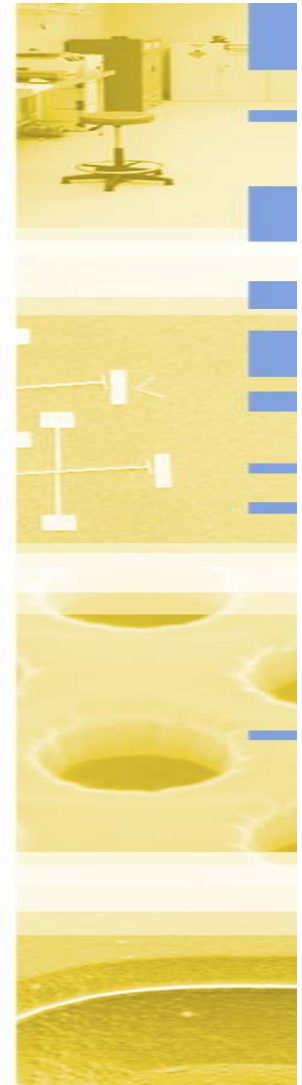
- ENIAC wafer technology roadmap
- Nanoroadmap (NRM) Project
- NanoRoad SME project
- Microfluidics roadmaps
- etc.



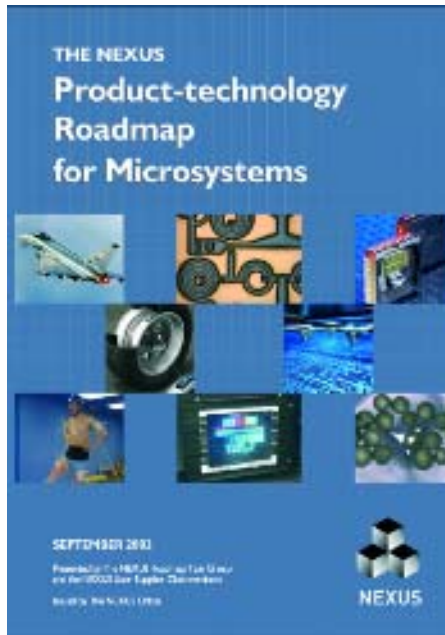
European Technology Platforms (MNT)

- EPoSS: Smart Systems Integration
- MINAM: Nanomanufacturing (within Manufuture Platform)
- ENIAC: Nanoelectronics
- ARTEMIS: Embedded Systems
- Photonics21
- Rapid Manufacturing
- Medical...
- more...

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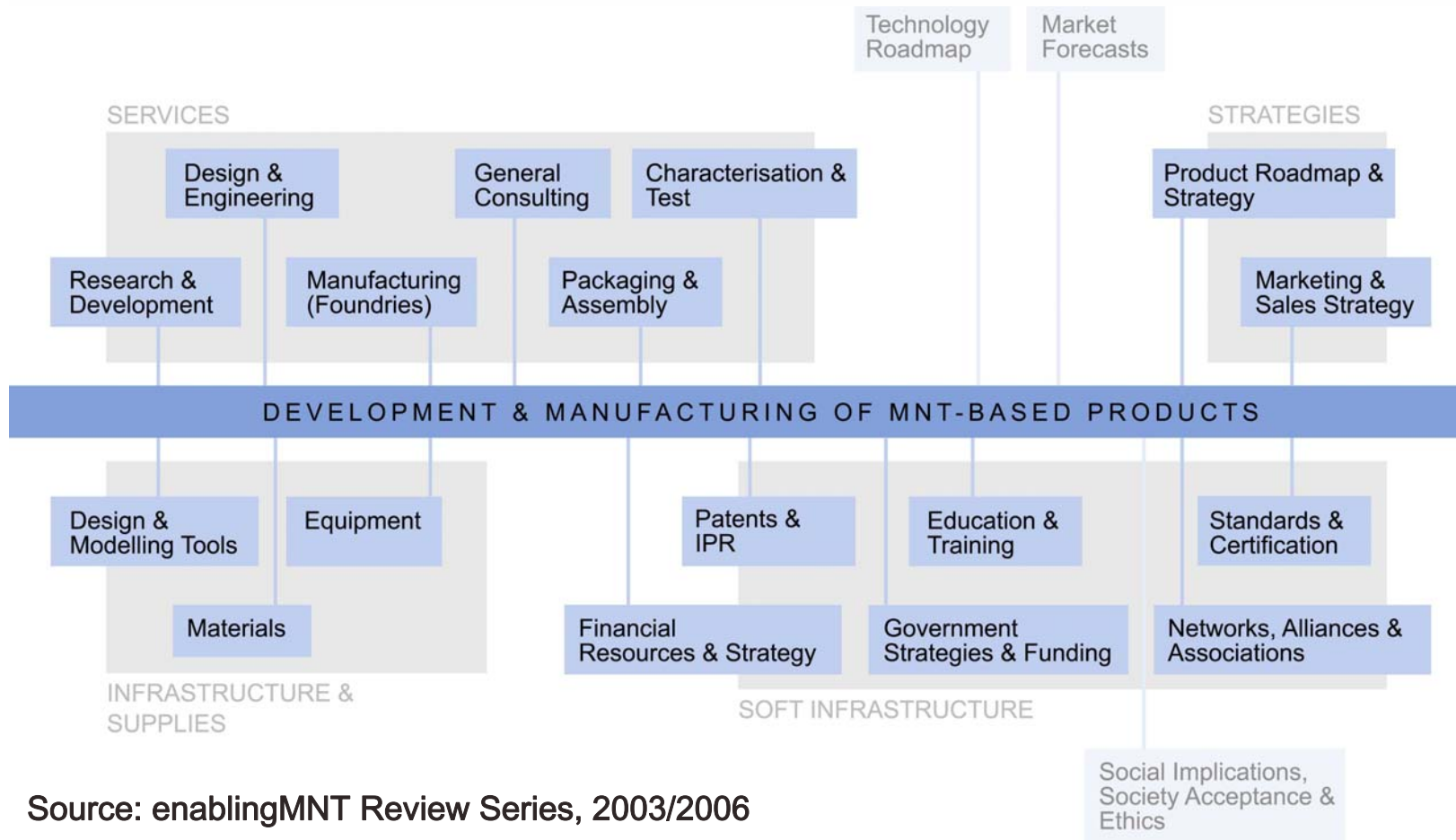
International Networks and Roadmapping Activities



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Supply Chain for MNT-based Products



Source: enablingMNT Review Series, 2003/2006

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Further Information

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NEXUS Roadmap Report

NEXUS Market Analysis (also available on CD now)

MANCEF Roadmap

enablingMNT Reports

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